

**PRESS RELEASE**

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**For Immediate Release**

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## **David K. Lam Honored at Engineer's Week Banquet** Founder of Lam Research inducted into Silicon Valley Engineering Hall of Fame

**SANTA CLARA, CA - Feb. 20, 2013** - Dr. David K. Lam and three other eminent technologists were honored last night at the Engineer's Week Banquet by being inducted into the Silicon Valley Engineering Hall of Fame. The annual induction and celebratory event was hosted by the Silicon Valley Engineering Council (SVEC), an umbrella organization of more than 20 member and affiliate professional societies representing 30,000 engineers, scientists and technologists in the region.

### **Inspired by Late Parents; Lam Research Retrospection**

In accepting his honor, Dr. Lam recognized the inspiration he received from his late father, a brilliant entrepreneur, and his late widowed mother, the first angel investor in Lam Research. He reflected on his father's experience in successfully expanding the market for Pilot writing pens in Asia. "While my father promoted pens that write on paper, I am now promoting advance electron-beam systems that write on semiconductor wafers."

Dr. Lam also cited striking similarities to what he is doing today at Multibeam Corporation to what he did at Lam Research in its early days. "Both companies endured tough economic times at the outset, and both were developing products that were initially perceived to be too slow for use in a production environment."

As CEO of Lam Research in the early 1980s, Dr. Lam guided the launch and market penetration of the company's first plasma etcher for semiconductor manufacturing, another type of capital equipment that effectively writes on wafers. Born in China, he became in 1984 the first Asian-American to take a company public on the NASDAQ market.

### **Complementary Technology Attributes**

Dr. Lam engrossed the engineering-minded audience by touching upon the importance of complementary technology, which has proved from time to time to enhance an existing technology in a cost-efficient way. "Unlike a disruptive technology that once adopted will quickly replace an existing technology, a well-conceived complementary technology works in harmony with an existing one, seamlessly extending its practical use and greatly benefiting the customer in performance and cost."

Dr. Lam noted that the semiconductor industry is ripe for a complementary technology to play a key role in keeping Moore's Law on track over the next decade. As one example, he cited recent advances in e-beam technology that now enable it to work hand-in-hand with existing optical lithography to print wafer patterns cost efficiently at single-nanometer nodes.

In his closing remarks, the renowned entrepreneur lauded the SVEC for its untiring effort to promote engineering education through its scholarship program. "To create an innovative complementary technology, you need top engineers."

## Hall of Fame Pantheon

The pantheon of technologists who have previously been inducted into the Silicon Valley Engineering Hall of Fame includes Intel co-founders Robert N. Noyce and Gordon E. Moore as well as Hewlett-Packard co-founders William R. Hewlett and David Packard. Joining Dr. Lam in being inducted last night were: Dr. Aart de Geus, Chairman of the Board and Co-CEO of Synopsys, Inc.; Dr. Martin Hellman, Professor Emeritus of Electrical Engineering, Stanford University; and Dr. David Hodges, Professor Emeritus, Dept. of Electrical Engineering and Computer Sciences, University of California, Berkeley.



**Dr. David K. Lam**  
*Founder of Lam Research, and currently  
Chairman of Multibeam Corporation and the David Lam Group*

## About Multibeam Corporation

Headquartered in Santa Clara, California, Multibeam Corporation is a leading developer of multi-column e-beam technologies that add high value to semiconductor lithography by doing away with costly masks. The company's Complementary E-Beam Lithography (CEBL) system augments optical lithography at critical layers by eliminating expensive optical multiple patterning at 20nm processing nodes and beyond. Multibeam's systems can also be cost-efficiently leveraged as primary lithographic tools for low-volume production of ASICs as well as in multi-project wafer programs. Multibeam's patent-protected e-beam technologies encompass deployment of multi-column arrays to perform wafer inspection.

For more information, visit [www.multibeamcorp.com](http://www.multibeamcorp.com).